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| <b>Notice of References Cited</b> | Application/Control No.<br>10/575,489 |  | Applicant(s)/Patent Under<br>Reexamination<br>FUKSHIMA ET AL. |             |
|                                   | Examiner<br>Minchul Yang              |  | Art Unit<br>2891  | Page 1 of 1 |

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